IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of / Julia S. SVIRCHEVSKI et al. Application No. 09/336,401 Filed: June 18, 1999 POST-PLASMA PROCESSING WAFER For:

Group Art Unit: 1765

Examiner: L. Umez-Eronini

Attorney Docket No. LAM1P109

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on November 27, 2000.

AMENDMENT

Assistant Commissioner for Patents Washington, DC 20231

Dear Sir:

Applicants submit this paper in response to the Office Action dated July 27, 2000. A response to this Office Action was due on October 27, 2000. Accordingly, Applicants are concurrently submitting a request for a one-month extension of the period for response. Please amend this application as follows:

IN THE SPECIFICATION:

Page 4, line 7: change "associate" to --associated--.

Page 15, line 8: charge "preformed" to --performed--.

IN THE CLAIMS:

Please carcel claims 12-20.

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